

| L Number | Hits | Search Text | DB | Time stamp |
|----------|------|---|------------------------------------|------------------|
| - | 1 | (."6451512").PN. | USPAT; US-PGPUB | 2003/06/28 12:30 |
| - | 3 | (("5563238") or ("3811931") or ("3676401")).PN. | USPAT; US-PGPUB | 2003/06/28 15:11 |
| - | 1862 | (resist or photoresist or photopolymer\$7) same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7) with (lactic or ketone or organometal\$3 or metal adj salt or siloxane or silane or hexamethyldisilazane or HMDS) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/06/28 15:29 |
| - | 1101 | ((resist or photoresist or photopolymer\$7) same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7) with (lactic or ketone or organometal\$3 or metal adj salt or siloxane or silane or hexamethyldisilazane or HMDS) and (semiconduct\$3 or semi adj conduct\$3 or wafer or silicon or "Si") same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/06/28 15:46 |
| - | 397 | ((resist or photoresist or photopolymer\$7) same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7) with (lactic or ketone or organometal\$3 or metal adj salt or siloxane or silane or hexamethyldisilazane or HMDS) and (semiconduct\$3 or semi adj conduct\$3 or wafer or silicon or "Si") same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7)) and (degrad\$4 or decompos\$5 or break\$3 or downgrad\$4 or deteriorat\$4 or disintegrat\$4 or decay\$3 or dissolv\$4 or fragment\$4) same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/06/28 15:47 |
| - | 42 | ((((resist or photoresist or photopolymer\$7) same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7) with (lactic or ketone or organometal\$3 or metal adj salt or siloxane or silane or hexamethyldisilazane or HMDS) and (semiconduct\$3 or semi adj conduct\$3 or wafer or silicon or "Si") same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7)) and (degrad\$4 or decompos\$5 or break\$3 or downgrad\$4 or deteriorat\$4 or disintegrat\$4 or decay\$3 or dissolv\$4 or fragment\$4) same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7)) and (430/311,319,327-329).ccls. | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/01/17 18:12 |

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|---|-----|---|------------------------------------|------------------|
| - | 355 | ((((resist or photoresist or photopolymer\$7) same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7) with (lactic or ketone or organometal\$3 or metal adj salt or siloxane or silane or hexamethyldisilazane or HMDS)) and (semiconduct\$3 or semi adj conduct\$3 or wafer or silicon or "Si") same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7)) and (degrad\$4 or decompos\$5 or break\$3 or downgrad\$4 or deteriorat\$4 or disintegrat\$4 or decay\$3 or dissolv\$4 or fragment\$4) same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7)) not (((((resist or photoresist or photopolymer\$7) same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7) with (lactic or ketone or organometal\$3 or metal adj salt or siloxane or silane or hexamethyldisilazane or HMDS)) and (semiconduct\$3 or semi adj conduct\$3 or wafer or silicon or "Si") same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7)) and (degrad\$4 or decompos\$5 or break\$3 or downgrad\$4 or deteriorat\$4 or disintegrat\$4 or decay\$3 or dissolv\$4 or fragment\$4) same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7)) and (430/311,319,327-329).ccls.) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/01/17 18:14 |
| - | 0 | ((light) near3 (degrad\$4) near3 (prim\$3 or adhes\$7) same (resist or photoresist)) not (((((resist or photoresist or photopolymer\$7) same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7) with (lactic or ketone or organometal\$3 or metal adj salt or siloxane or silane or hexamethyldisilazane or HMDS)) and (semiconduct\$3 or semi adj conduct\$3 or wafer or silicon or "Si") same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7)) and (degrad\$4 or decompos\$5 or break\$3 or downgrad\$4 or deteriorat\$4 or disintegrat\$4 or decay\$3 or dissolv\$4 or fragment\$4) same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7)) not (((((resist or photoresist or photopolymer\$7) same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7) with (lactic or ketone or organometal\$3 or metal adj salt or siloxane or silane or hexamethyldisilazane or HMDS)) and (semiconduct\$3 or semi adj conduct\$3 or wafer or silicon or "Si") same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7)) and (degrad\$4 or decompos\$5 or break\$3 or downgrad\$4 or deteriorat\$4 or disintegrat\$4 or decay\$3 or dissolv\$4 or fragment\$4) same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7)) and (430/311,319,327-329).ccls.) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/01/17 18:15 |
| - | 0 | ((light) near3 (degrad\$4) near3 (prim\$3 or adhes\$7) same (resist or photoresist)) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/01/17 18:15 |
| - | 12 | ((light) near3 (degrad\$4) near3 (prim\$3 or adhes\$7) and (resist or photoresist)) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/01/17 18:16 |
| - | 0 | ((light) near3 (degrad\$4) with (primer or priming) same (resist or photoresist)) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/01/17 18:17 |

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| - | 88 | ((bilayer or bi adj layer) same positive near2 (resist or photoresist)) | USPAT; US-PGPUB; EPO; JPO; IBM TDB USPAT; | 2003/07/16 16:27 |
| - | 74 | ((bilayer or bi adj layer) same positive near2 (resist or photoresist))) and (thick or thickness) same (resist or photoresist) | USPAT; US-PGPUB; EPO; JPO; IBM TDB USPAT; | 2004/01/17 18:17 |
| - | 2 | ((hexamethyldisilazane or HMDS) near5 decompos\$4) same (resist or photoresist) | USPAT; US-PGPUB; EPO; JPO; IBM TDB USPAT; | 2004/01/17 18:18 |
| - | 12 | ((hexamethyldisilazane or HMDS) near5 (light or uv)) same (resist or photoresist) | USPAT; US-PGPUB; EPO; JPO; IBM TDB USPAT; | 2004/01/17 18:18 |
| - | 92 | (134/1.3).ccls. and (light or uv) same (resist or photoresist) | USPAT; US-PGPUB; EPO; JPO; IBM TDB USPAT; | 2003/07/18 15:34 |
| - | 6 | ((134/1.3).ccls. and (light or uv) same (resist or photoresist)) and (hexamethyldisilazane or HMDS) | USPAT; US-PGPUB; EPO; JPO; IBM TDB USPAT; | 2004/01/17 18:19 |
| - | 17 | ((hexamethyldisilazane or HMDS) near5 (light or uv or ultraviolet)) same (resist or photoresist) | USPAT; US-PGPUB; EPO; JPO; IBM TDB USPAT; | 2004/01/17 18:19 |
| - | 16 | (light or uv or ultraviolet) same ((bond\$3 or coupl\$3) near2 (strength or energy)) same ((silicon or Si) near5 (oxygen)) | USPAT; US-PGPUB; EPO; JPO; IBM TDB USPAT; | 2004/01/17 18:20 |
| - | 19 | (light or uv or ultraviolet) same ((bond\$3 or coupl\$3) near2 (strength or energy)) same ("Si--O" or "O--Si") | USPAT; US-PGPUB; EPO; JPO; IBM TDB USPAT; | 2004/01/17 18:20 |
| - | 47 | (((resist or photoresist or photopolymer\$7) same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7) with (lactic or ketone or organometal\$3 or metal adj salt or siloxane or silane or hexamethyldisilazane or HMDS)) and (semiconduct\$3 or semi adj conduct\$3 or wafer or silicon or "Si") same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7)) and (degrad\$4 or decompos\$5 or break\$3 or downgrad\$4 or deteriorat\$4 or disintegrat\$4 or decay\$3 or dissolv\$4 or fragment\$4) same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7)) and (430/311,319,327-329).ccls. | USPAT; US-PGPUB; EPO; JPO; IBM TDB | 2004/01/17 18:13 |

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|---|-----|---|------------------------------------|------------------|
| - | 405 | ((((resist or photoresist or photopolymer\$7) same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7) with (lactic or ketone or organometal\$3 or metal adj salt or siloxane or silane or hexamethyldisilazane or HMDS)) and (semiconduct\$3 or semi adj conduct\$3 or wafer or silicon or "Si") same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7) not (((resist or photoresist or photopolymer\$7) same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7) with (lactic or ketone or organometal\$3 or metal adj salt or siloxane or silane or hexamethyldisilazane or HMDS)) and (semiconduct\$3 or semi adj conduct\$3 or wafer or silicon or "Si") same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7)) and (degrad\$4 or decompos\$5 or break\$3 or downgrad\$4 or deteriorat\$4 or disintegrat\$4 or decay\$3 or dissolv\$4 or fragment\$4) same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7)) not (((resist or photoresist or photopolymer\$7) same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7) with (lactic or ketone or organometal\$3 or metal adj salt or siloxane or silane or hexamethyldisilazane or HMDS)) and (semiconduct\$3 or semi adj conduct\$3 or wafer or silicon or "Si") same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7)) and (degrad\$4 or decompos\$5 or break\$3 or downgrad\$4 or deteriorat\$4 or disintegrat\$4 or decay\$3 or dissolv\$4 or fragment\$4) same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7)) and (430/311,319,327-329).ccls.) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/01/17 18:14 |
| - | 0 | ((light) near3 (degrad\$4) near3 (prim\$3 or adhes\$7) same (resist or photoresist)) not (((resist or photoresist or photopolymer\$7) same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7) with (lactic or ketone or organometal\$3 or metal adj salt or siloxane or silane or hexamethyldisilazane or HMDS)) and (semiconduct\$3 or semi adj conduct\$3 or wafer or silicon or "Si") same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7)) and (degrad\$4 or decompos\$5 or break\$3 or downgrad\$4 or deteriorat\$4 or disintegrat\$4 or decay\$3 or dissolv\$4 or fragment\$4) same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7)) not (((resist or photoresist or photopolymer\$7) same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7) with (lactic or ketone or organometal\$3 or metal adj salt or siloxane or silane or hexamethyldisilazane or HMDS)) and (semiconduct\$3 or semi adj conduct\$3 or wafer or silicon or "Si") same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7)) and (degrad\$4 or decompos\$5 or break\$3 or downgrad\$4 or deteriorat\$4 or disintegrat\$4 or decay\$3 or dissolv\$4 or fragment\$4) same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7)) not (((resist or photoresist or photopolymer\$7) same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7) with (lactic or ketone or organometal\$3 or metal adj salt or siloxane or silane or hexamethyldisilazane or HMDS)) and (semiconduct\$3 or semi adj conduct\$3 or wafer or silicon or "Si") same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7)) and (degrad\$4 or decompos\$5 or break\$3 or downgrad\$4 or deteriorat\$4 or disintegrat\$4 or decay\$3 or dissolv\$4 or fragment\$4) same (coupl\$3 or bond\$3 or prim\$3 or adhes\$7)) and (430/311,319,327-329).ccls.) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/01/17 18:15 |
| - | 0 | ((light) near3 (degrad\$4) near3 (prim\$3 or adhes\$7) same (resist or photoresist)) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/01/17 18:16 |
| - | 13 | ((light) near3 (degrad\$4) near3 (prim\$3 or adhes\$7) and (resist or photoresist)) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/01/17 18:16 |
| - | 0 | ((light) near3 (degrad\$4) with (primer or priming) same (resist or photoresist)) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/01/17 18:17 |

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| | 83 | ((bilayer or bi adj layer) same positive near2 (resist or photoresist))) and (thick or thickness) same (resist or photoresist) | USPAT; US-PGPUB; EPO; JPO; IBM TDB | 2004/01/17 18:17 |
| | 2 | ((hexamethyldisilazane or HMDS) near5 decompos\$4) same (resist or photoresist) | USPAT; US-PGPUB; EPO; JPO; IBM TDB | 2004/01/17 18:18 |
| | 15 | ((hexamethyldisilazane or HMDS) near5 (light or uv)) same (resist or photoresist) | USPAT; US-PGPUB; EPO; JPO; IBM TDB | 2004/01/17 18:18 |
| | 6 | ((134/1.3).ccls. and (light or uv) same (resist or photoresist)) and (hexamethyldisilazane or HMDS) | USPAT; US-PGPUB; EPO; JPO; IBM TDB | 2004/01/17 18:19 |
| | 20 | ((hexamethyldisilazane or HMDS) near5 (light or uv or ultraviolet)) same (resist or photoresist) | USPAT; US-PGPUB; EPO; JPO; IBM TDB | 2004/01/17 18:20 |
| | 19 | (light or uv or ultraviolet) same ((bond\$3 or coupl\$3) near2 (strength or energy)) same ((silicon or Si) near5 (oxygen)) | USPAT; US-PGPUB; EPO; JPO; IBM TDB | 2004/01/17 18:20 |
| | 20 | (light or uv or ultraviolet) same ((bond\$3 or coupl\$3) near2 (strength or energy)) same ("Si--O" or "O--Si") | USPAT; US-PGPUB; EPO; JPO; IBM TDB | 2004/01/17 18:20 |
| | 20 | (polydimethylglutarimide or polymethylglutarimide or polyglutarimide or PMGI) same (polar\$3 or nonpolar\$3 or hydrophilic or hydrophobic) | USPAT; US-PGPUB; EPO; JPO; IBM TDB | 2004/01/20 19:50 |